

PATENT



F0601 (AMDP6)

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Date: 3-27-02

Himanshu S. Amin

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of:

Applicants: Arvind Halliyal

Serial No: 09/804,283

Filing Date: March 12, 2001

Examiner: Deven M. Collins

Art Unit: 2823

Title: IN SITU MONITORING OF SHEET RESISTIVITY OF SILICIDES DURING RAPID THERMAL ANNEALING USING ELECTRICAL METHODS

Assistant Commissioner for Patents
U.S. Patent and Trademark Office
Washington, D.C. 20231

REPLY TO RESTRICTION REQUIREMENT MAILED MARCH 18, 2002

This Reply is in response to the Restriction Requirement mailed on March 18, 2002 in connection with the above-identified patent application.

The Examiner requires restriction to one of the following two groups of claims:

(I) claims 20 to 23 or (II) claims 1-19 and 24-26.

Applicants hereby elect with traverse group II (claims 1-19 and 24-26 drawn to system for analyzing sheet resistivity) for further prosecution on the merits.

09/804,283

F0601(AMDP601US)

Should there be any questions regarding this paper, the Examiner is invited to contact applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,

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